

FORM PTO-1449		Docket Number (Optional) 005586/D-8326		Parent Application Number 08/912,505		
<b>INFORMATION DISCLOSURE CITATION IN AN APPLICATION</b>		Applicant Hidenori Ogata et al.				
(Use several sheets if necessary)		Parent Filing Date August 14, 1997		Parent Group Art Unit 2822		
<b>U.S. PATENT DOCUMENTS</b>						
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
MW	5,432,122	7/1995	Chae			
MW	5,496,768	3/1996	Kudo			
MW	4,234,358	11/1980	Celler et al.			
MW	5,365,875	11/1994	Asai et al.			
MW	5,683,935	11/1997	Miyamoto et al.			
MW	5,529,951	6/1996	Noguchi et al.			
MW	5,591,668	6/1997	Maegawa et al.			
MW	4,514,895	5/1985	Nishimura			
MW	5,815,494	9/1998	Yamazaki et al.			
MW	5,767,003	6/1998	Noguchi			
MW	5,454,347	10/1995	Shibata et al.			
MW	5,533,040	7/1996	Zhang			
<b>FOREIGN PATENT DOCUMENTS</b>						
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION (YES/NO)
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>						
MW	M. Kamiya et al., "Eximer Laser Annealing SLA3600," pp. 24-25 with its English translations and Document 1 (Electronic Display Forum '96 program cover sheet, April 17-19, 1996) and Document 2 (List of presentations at Forum '96, including "Eximer Laser Annealing System SLA 3600, April 19, No. 18) showing the laid open date of 4/17-4/19/1996					
MW	Mamoru Furuta et al., "Bottom-Gate Poly-Si Thin Film Transistors Using XeCl Excimer Laser Annealing and Ion Doping Techniques," <i>IEEE Transactions on Electron Devices</i> , vol. 40, No. 11, November, 1993					
EXAMINER MWileczewski		DATE CONSIDERED 6/02				
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.						

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 09/29/98  
 04/14/99